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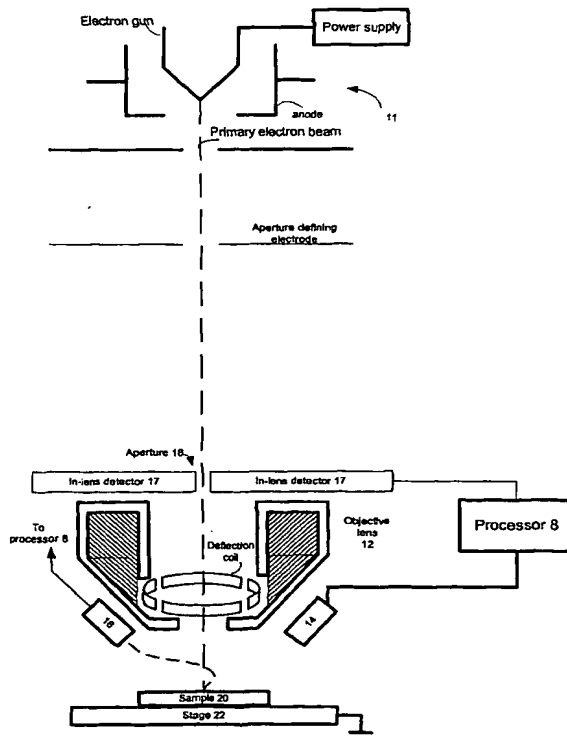
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[Continued on next page]

(54) Title: METHODS AND SYSTEMS FOR PROCESS MONITORING USING X-RAY EMISSION



(57) Abstract: Systems and methods for process monitoring based upon X-ray emission induced by a beam of charged particles such as electrons or ions. Concept as expressed herein.

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